

Electronic Supplementary Information

1D conical nanotubular TiO₂ / CdS heterostructure for superior photon-to-electron conversion

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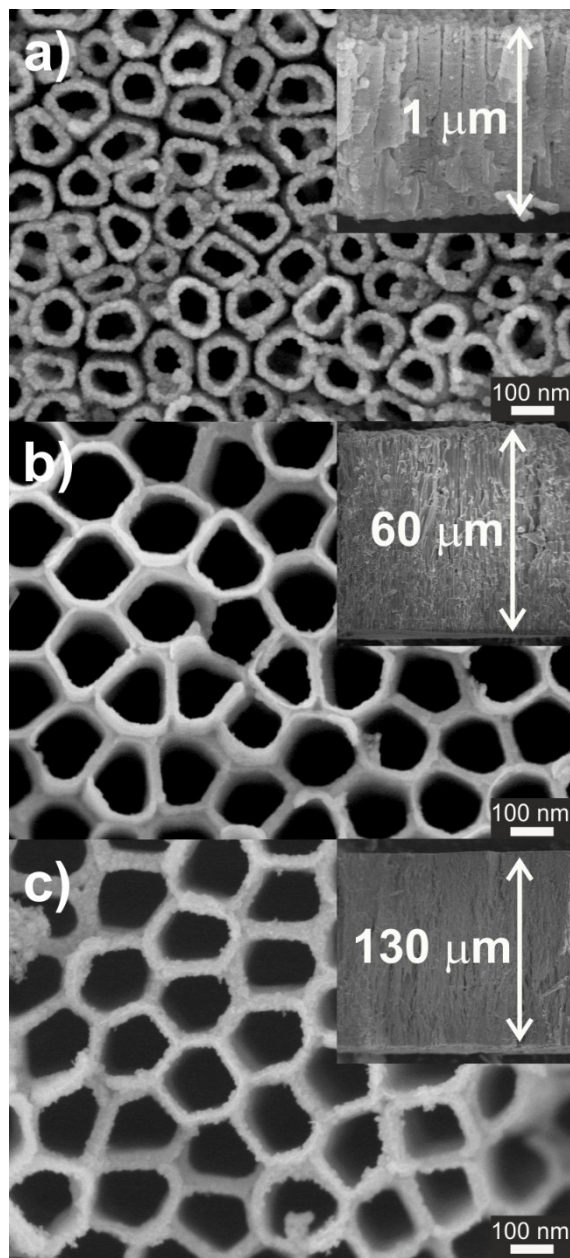


Fig. S1. SEM top view images of the CdS coated (5 nm) TiO₂ nanotube layers of different thickness: 1 μm (a, b) 60 μm (c, d) and 130 μm (e, f). Insets: cross-sectional SEM images of the corresponding TiO₂ nanotube layers.

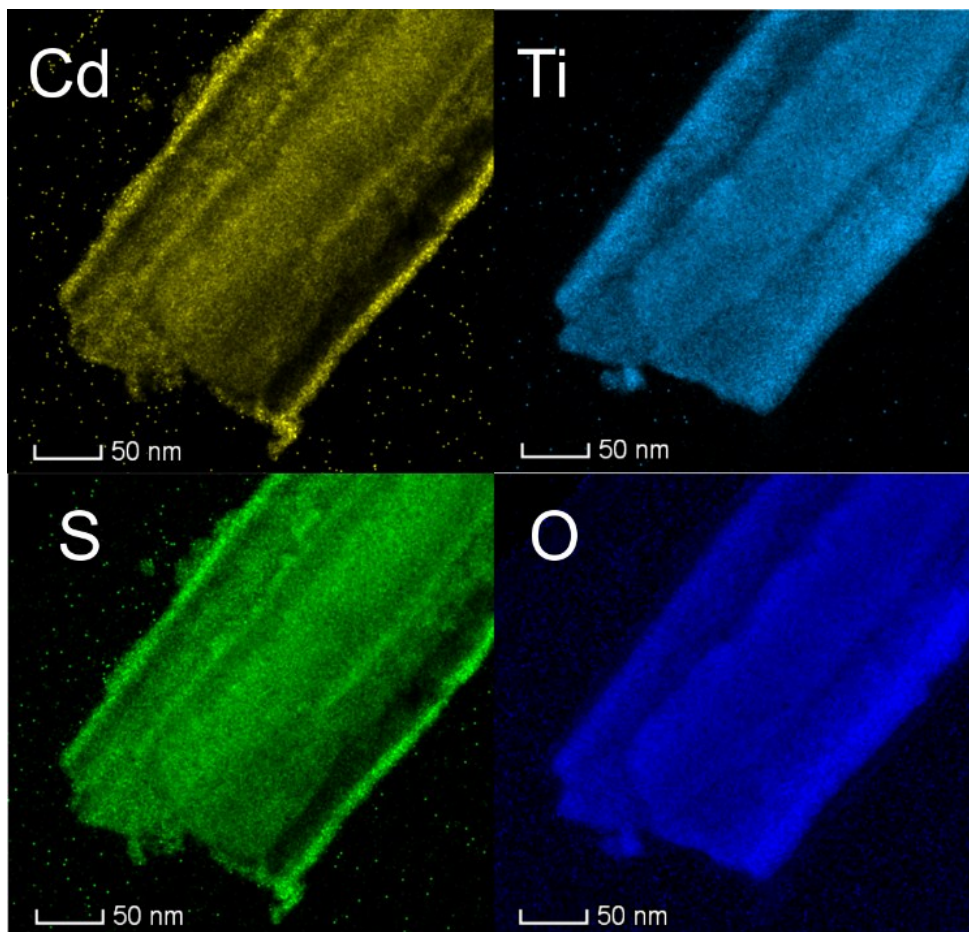


Fig. S2. Elemental STEM/EDX maps of a fragment of a single 130 μm TiO_2 nanotube coated with 5 nm of CdS.

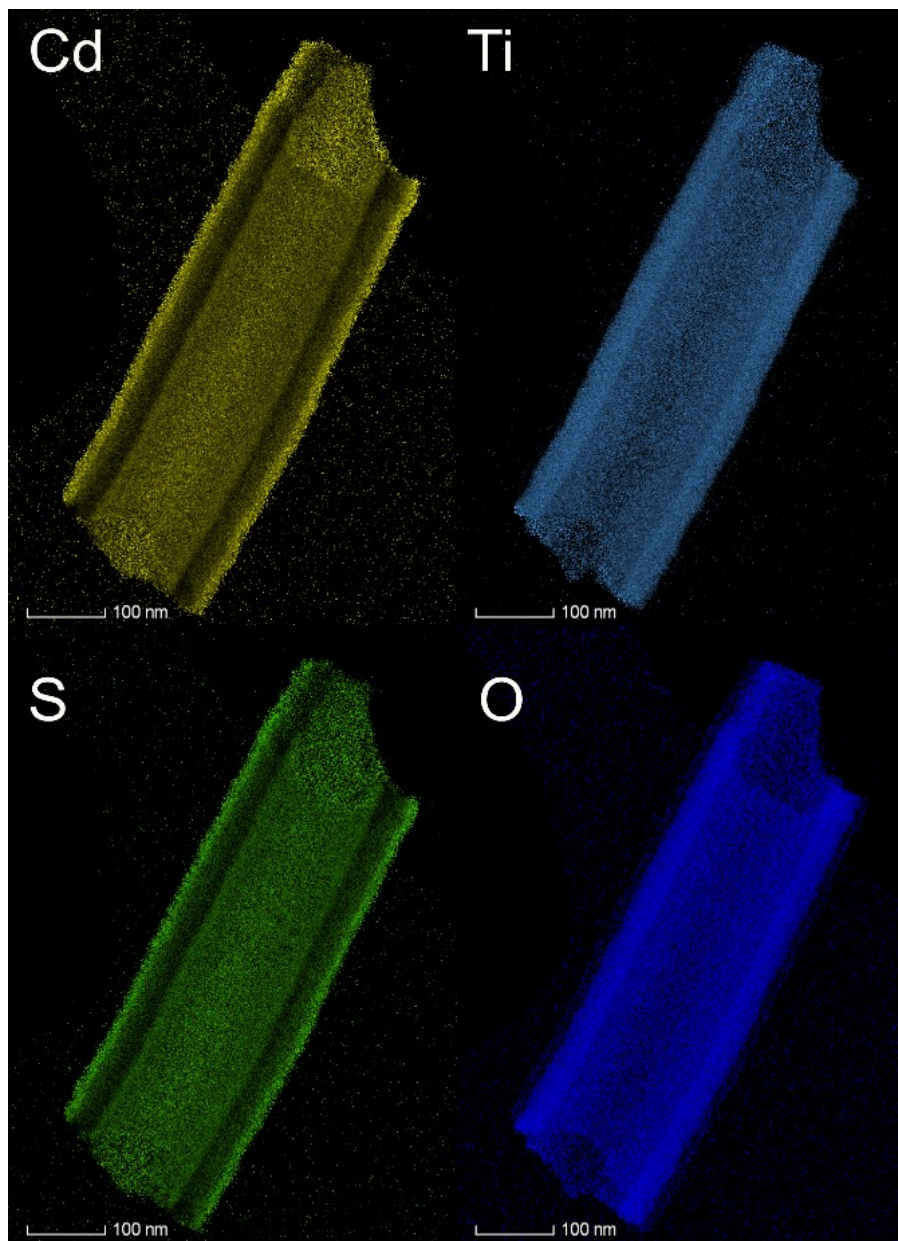


Fig. S3. Elemental STEM/EDX maps of a fragment of a single 20 μm TiO₂ nanotube coated with 10 nm of CdS.

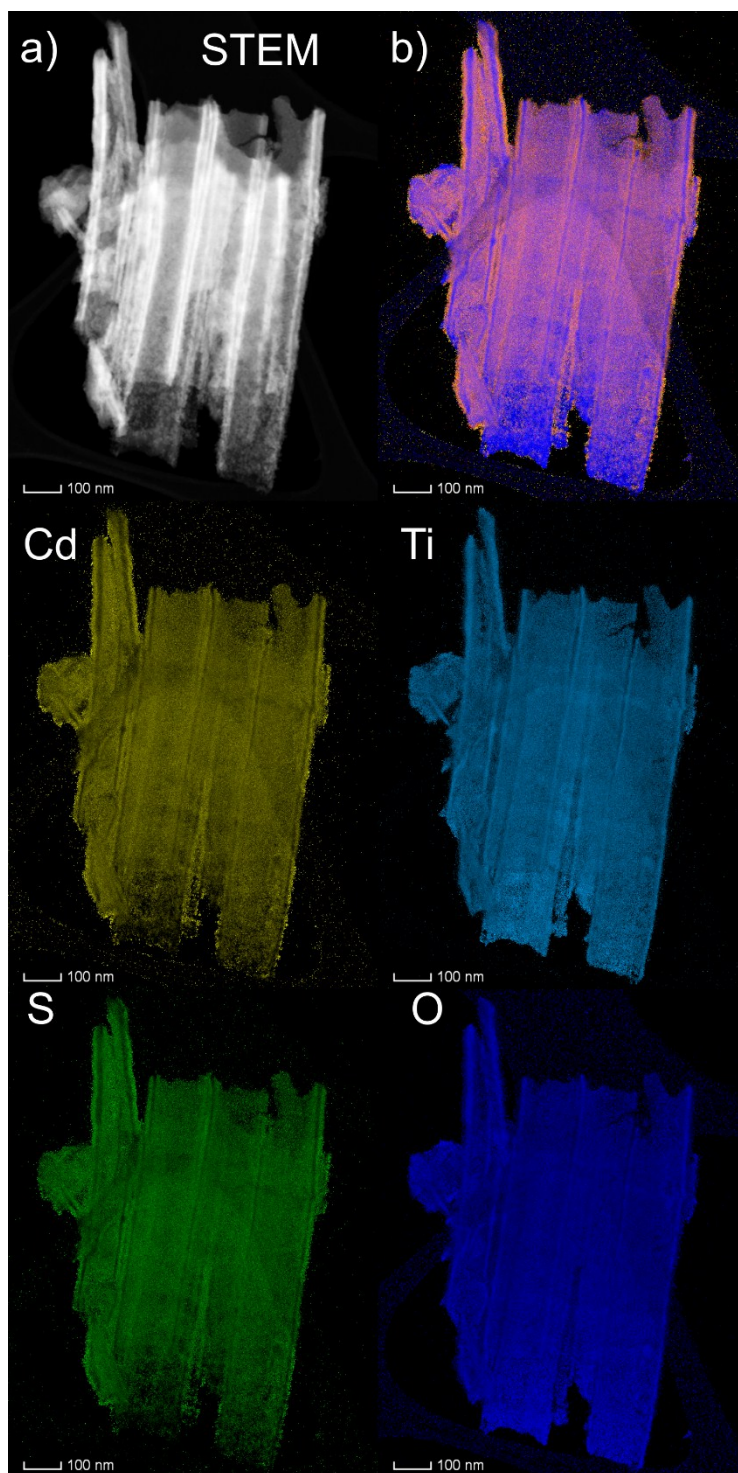


Fig. S4. A HAADF-STEM image of (a) a bundle of 130 μm thick TiO_2 nanotube layer coated with 5 nm of CdS, and (b) corresponding overall STEM/EDX elemental map. Other images show STEM/EDX maps for individual elements.

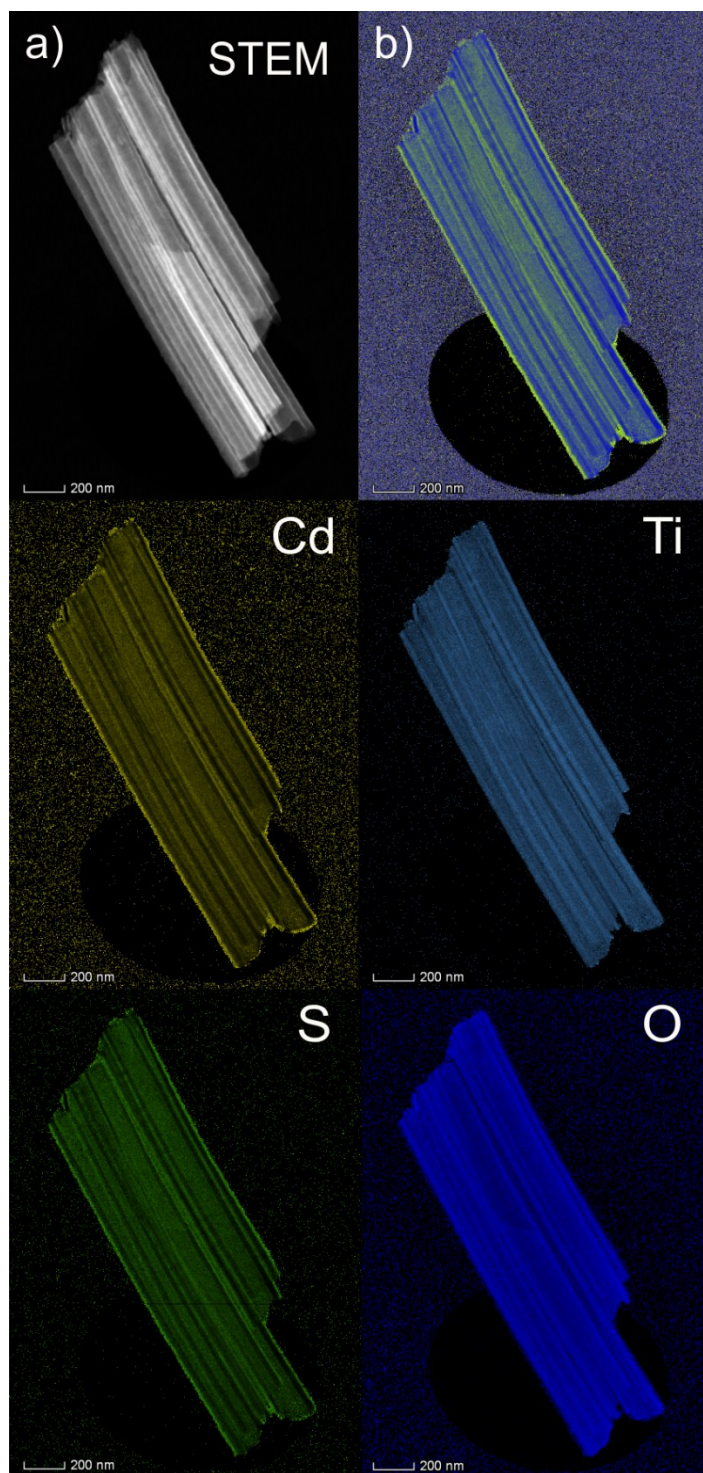


Fig. S5. A HAADF-STEM image of (a) a bundle of 20 μm thick TiO_2 nanotube layer coated with 10 nm of CdS, and (b) corresponding overall STEM/EDX elemental map. Other images show STEM/EDX maps for individual elements.

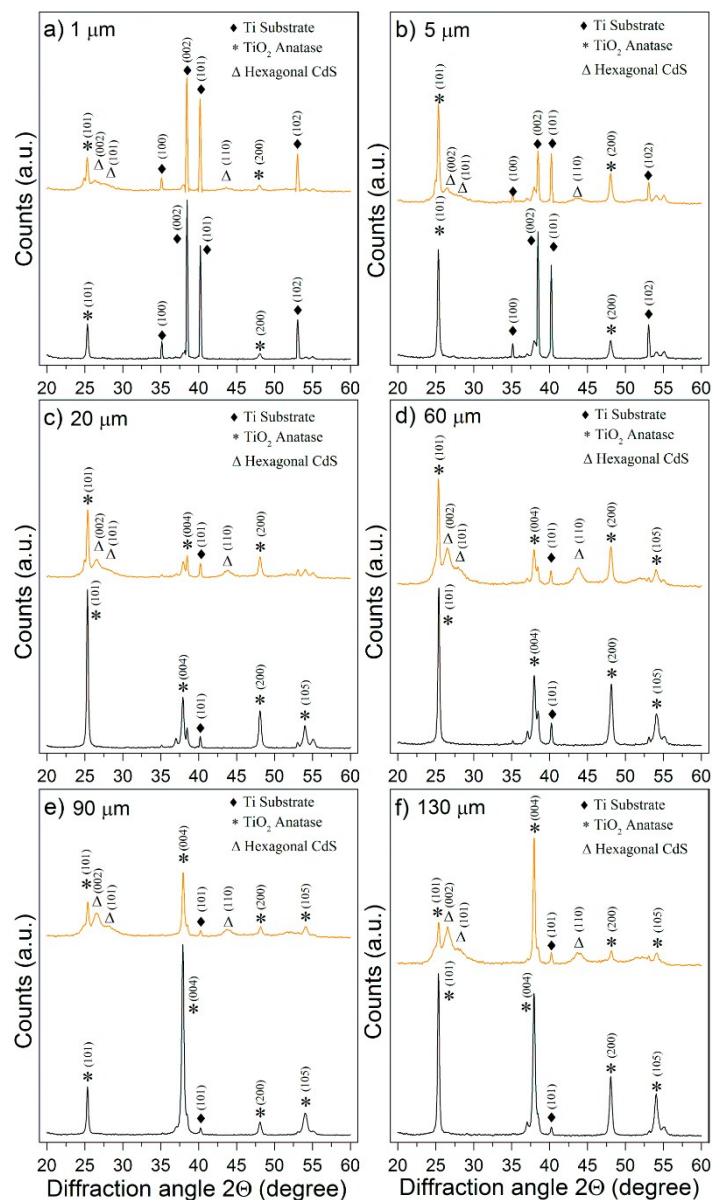


Fig. S6. XRD patterns of blank (lower black lines) and CdS coated (upper orange lines) TiO₂ nanotube layers (a) 1 μm, (b) 5 μm, (c) 20 μm, (d) 60 μm, (e) 90 μm, and (f) 130 μm thick.

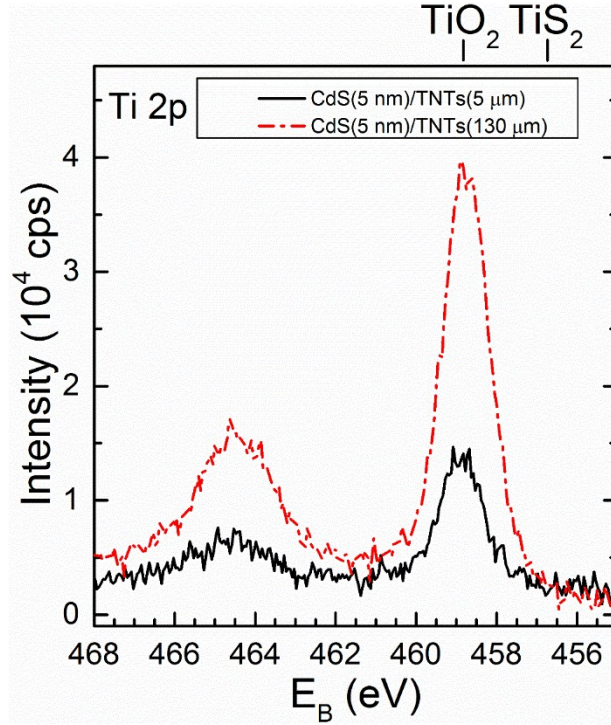


Fig. S7. XPS Ti 2p spectra of CdS coated TiO₂ nanotube layers 1 μm (black solid line) and 130 μm thick (red dashed line). The binding energy of Ti-O and Ti-S bonds are indicated at the top axis. The spectra show the absence of Ti-S bond.

CdS/TNT band alignment determined by XPS

The band offsets at the CdS/TiO₂ interface were determined by XPS following the concept introduced by Kraut et al. [1]. The valence band offset (VBO) at CdS/TiO₂ interface was determined according to following relation:

$$VBO = - (EB_{Ti2p} - VBM_{TiO_2})^{(i)} + (EB_{Cd3d} - VBM_{CdS})^{(ii)} + (EB_{Ti2p} - EB_{Cd3d})^{(iii)} \quad (1)$$

where EB_{Ti2p} and EB_{Cd3d} are binding energies of Ti 2p_{3/2} and Cd 3d_{5/2} core level lines, respectively, and VBM_{TiO_2} and VBM_{CdS} are valence band maxima of TiO₂ and CdS, respectively, collected from TiO₂ reference, CdS reference, and CdS/TiO₂ interface as illustrated

in Fig. S8. Blank, 2.5 nm CdS coated, and 10 nm CdS coated TNT layers were used as TiO₂ reference, interface, and CdS reference, respectively. Based on obtained values listed in Table S1 the valence band of TiO₂ is found to lie (1.2 ± 0.2) eV below valence band of CdS at CdS/TiO₂ interface. The conduction band offset (CBO) was calculated using the conventional bulk band gap values of anatase TiO₂ (3.2 eV) and CdS (2.4 eV) to be (0.4 ± 0.2) eV.

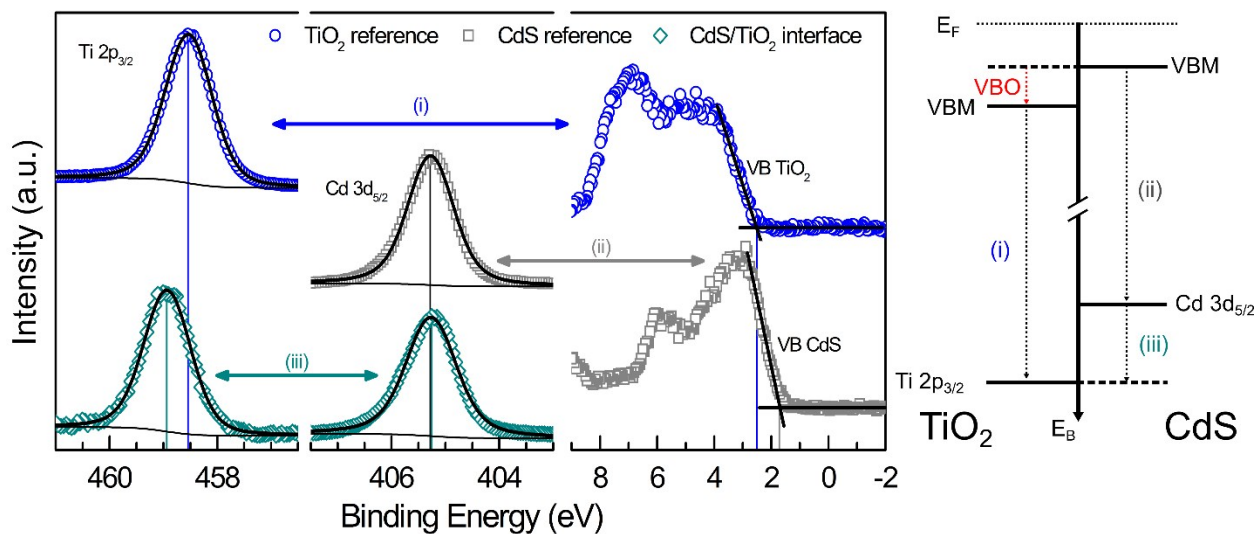


Fig. S8: Determination of valence band offset at CdS/TiO₂ interface using XPS. Valence band offset calculated based on binding energies of Ti2p_{3/2} and Cd 3d_{5/2} core levels and valence band maxima measured on TiO₂ reference, CdS reference, and CdS/TiO₂ interface.

Table S1: Binding energy values obtained by XPS from CdS reference, TiO₂ reference, and CdS/TiO₂ interface for calculation of valence and conduction band offsets.

	Binding Energy (eV)		
	Ti 2p _{3/2}	Cd 3d _{5/2}	VBM
CdS reference	x	405.26	1.70
TiO₂ reference	458.53	x	2.52
CdS/TiO₂ interface	458.93	405.27	x

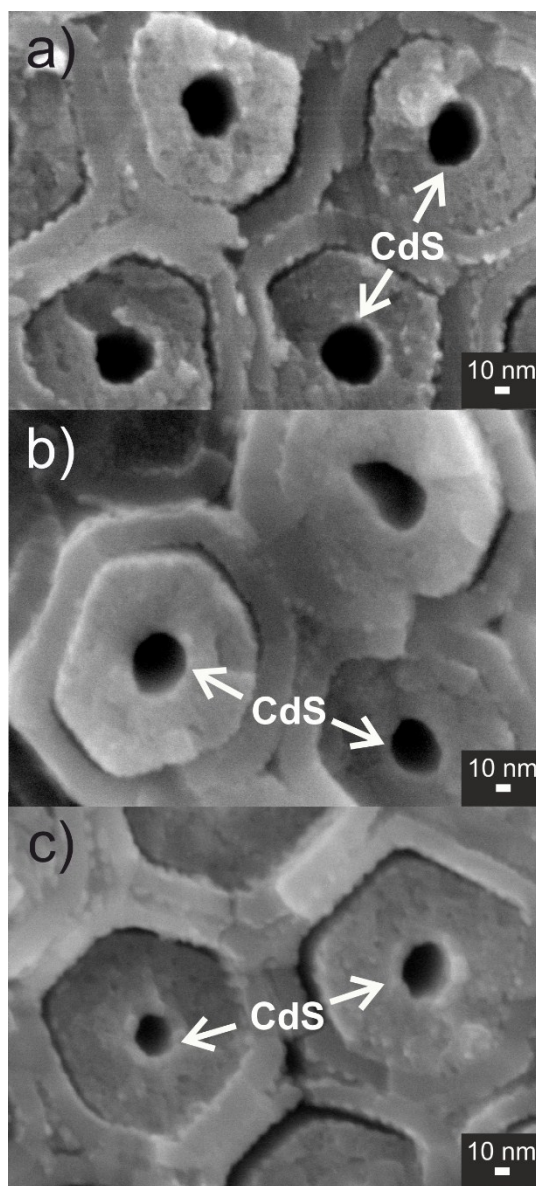


Fig. S9. SEM images of the bottom part of 20 μm thick TiO_2 nanotube layers with CdS coating of different thickness: a) 2.5 nm, b) 5 nm, and c) 10 nm.

References

1 E. A. Kraut, R. W. Grant, J. R. Waldrop, and S. P. Kowalczyk, in *Precise Determination of the Valence-Band Edge in X-Ray Photoemission Spectra: Application to Measurement of Semiconductor Interface Potentials*, Phys. Rev. Lett., 1980, 44, pp. 1620–1623.